

# Tailoring of Two-dimensional Electron Gas Density in Thin Film Oxide Heterostructure via Atomic Layer Deposition

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## Extended Abstract

Recently, oxide heterostructure-based two-dimensional electron gas (2DEG) has received intensive attentions owing to their interesting properties. The model system is epitaxial LaAlO<sub>3</sub> (LAO) grown on single crystalline SrTiO<sub>3</sub> (STO) substrate.[1] Electrons with a density of 10<sup>13</sup>~10<sup>14</sup>/cm<sup>2</sup> were observed which moves freely along in-plane direction while they are confined within ~2 nm (out-of-plane direction). Unfortunately, the adjustment of electron density was not available for the epitaxial LAO/STO heterostructure. In addition, the growth of epitaxial LAO film requires a high-temperature process (700 ~ 800°C) using pulsed laser deposition technique.

Here, we demonstrated a creation and control of 2DEG at the interface of non-epitaxial Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> thin film heterostructure using atomic layer deposition (ALD). The electron density can be tailored from ~ 10<sup>11</sup>/cm<sup>2</sup> to ~ 10<sup>14</sup>/cm<sup>2</sup> by the control of ALD process temperature because the electrons are coming from oxygen vacancies at the interface of Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> heterostructure of which oxygen vacancy density is governed by kinetics during the ALD process. Electron density up to ~10<sup>14</sup>/cm<sup>2</sup> was achieved at the interface of the Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> heterostructure which is 100 times higher than that of the conventional semiconductor heterojunction such as AlGaAs/GaAs.

The 2DEG at Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> heterostructure can be applied for the development hydrogen (H<sub>2</sub>) gas sensor. A high-performance, transparent, and extremely thin (<15 nm) hydrogen gas sensor was fabricated using 2DEG at the interface of Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> heterostructure grown by ALD. [2] Palladium nanoparticles (~2 nm in thickness) are used on the surface of the Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> thin film heterostructure to detect H<sub>2</sub>. Both oxides with a wide bandgap (>3.2 eV) have transmittance of 83% in the visible spectrum, which allows for a transparent sensor. The Pd/Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> gas sensor detects H<sub>2</sub> gas quickly with a short response time of <30 s even at room temperature which outperforms conventional H<sub>2</sub> gas sensors. This sensor responds to a wide range of H<sub>2</sub> concentration, especially from ~5 ppm to 1%, implying a promising candidate for a general H<sub>2</sub> sensor. Interestingly, the Pd/Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> gas sensor showed an optimal electron density for H<sub>2</sub> detection owing to the tailoring ability of 2DEG at the Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2</sub> heterostructure. Particularly, a sensitivity was as low as 3% for a 2DEG density of 5.6 × 10<sup>13</sup> cm<sup>-2</sup> while the sensitivity was improved from 6% to 43% as the electron density decreased from 5.6 × 10<sup>13</sup> cm<sup>-2</sup> to 4.1 × 10<sup>11</sup> cm<sup>-2</sup>. Besides the sensor application, other application of 2DEG will be introduced in the presentation.

## References

- [1] A. Ohtomo and H. Y. Hwang, "A high-mobility electron gas at the LaAlO<sub>3</sub>/SrTiO<sub>3</sub> heterointerface," *Nature*, vol. 427, pp. 423–426, 2004.
- [2] Sung Min Kim, Hye Ju Kim, Hae Jun Jung, Ji-Yong Park, Tae Jun Seok, Yong-Ho Choa, Tae Joo Park, Sang Woon Lee, "High-Performance, Transparent Thin Film Hydrogen Gas Sensor Using 2D Electron Gas at Interface of Oxide Thin Film Heterostructure Grown by Atomic Layer Deposition," *Advanced Functional Materials*, vol. 29, p. 1807760, 2019.